

1 IN THE UNITED STATES PATENT AND TRADEMARK OFFICE
2 BEFORE THE PATENT TRIAL AND APPEAL BOARD

3 _____
4 TAIWAN SEMICONDUCTOR
5 MANUFACTURING COMPANY, LTD.

6 AND TSMC NORTH AMERICA CORP.,

Case Nos.

IPR2014-00781

7 Petitioners,

IPR2014-00782

IPR2014-01083

8 -vs-

IPR2014-01086

IPR2014-01087

9 ZOND, LLC,

10 Patent Owner.

11 _____
12 VIDEOTAPED DEPOSITION of DR. UWE KORTSHAGEN

13 VOLUME I

14 Minneapolis, Minnesota

15 December 3rd, 2014

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17
18
19
20
21
22
23
24 Reported by:

Amy L. Larson, RPR

25 Job No. 87857

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 ///

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 2 EXAMINATION BY: PAGE
 3 Mr. Lahav.....9
 4 EXHIBITS MARKED FOR IDENTIFICATION:
 5 Exhibit 2004.....95
 6 U.S. Patent No. 6,398,929 B1
 7 No Bates
 8 PREVIOUSLY MARKED EXHIBITS:
 9 Exhibit TSMC 1001
 10 U.S. Patent No. 6,853,142 B2
 11 No Bates
 12 Exhibit INTEL 1002
 13 Kortshagen Declaration - '759 Patent
 14 No Bates
 15 Exhibit TSMC 1003
 16 High-Current Low-Pressure Quasi-Stationary
 17 Discharge in a Magnetic Field
 18 Experimental Research
 19 No Bates
 20 Exhibit TSMC 1004
 21 U.S. Patent No. 6,190,512 B1
 22 No Bates
 23 Exhibit TSMC 1201
 24 U.S. Patent No. 7,147,759 B2
 25 No Bates
 Exhibit TSMC 1202
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 Exhibit TSMC 1204
 Ionization Relaxation in a plasma produced
 by a pulsed inert-gas discharge
 No Bates
 Exhibit TSMC 1205
 U.S. Patent 6,413,382 B1
 No Bates

1 APPEARANCES: (CONT'D.)
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1 INDEX: (CONT'D.)
 2 PREVIOUSLY MARKED EXHIBITS:
 3 Exhibit TSMC 1216
 4 U.S. Patent 6,306,265 B1
 5 No Bates
 6 Exhibit TSMC 1221
 7 U.S. Patent 5,247,531
 8 No Bates
 9 Exhibit TSMC 1222
 10 European Patent Application
 11 No Bates
 12 Exhibit TSMC 1302
 13 Kortshagen Declaration - '759 Patent
 14 No Bates
 15 Exhibit
 16 Paper 13 - No Bates

1 THE VIDEOTAPED DEPOSITION OF DR. UWE KORTSHAGEN,
2 VOLUME I, taken on this 3rd day of December, 2014,
3 at The Commons Hotel, 615 Washington Avenue, S.E.,
4 Minneapolis, Minnesota, commencing at
5 approximately 7:37 a.m.

6
7 PROCEEDINGS

8
9 THE VIDEOGRAPHER: This is the
10 start of tape number 1 in the videotaped
11 deposition of Dr. Uwe Kortshagen in the
12 matter of Taiwan Semiconductor Manufacturing
13 Company, LL -- LTD, et al. Versus Zond, LLC,
14 in the United States Patent and Trademark
15 Office before the Patent Trial and Appeal
16 Board, case numbers IPR 2014-00781,
17 IPR 2014-00782, IPR 2014-01083,
18 IPR 2014-01086, and IPR 2014-01087.

19 This deposition is being held at the
20 Commons Hotel in Minneapolis, Minnesota, on
21 December 3rd, 2014, at approximately
22 7:41 a.m.

23 My name is Dean Hibben, I'm the legal
24 video specialist from TSG Reporting,
25 Incorporated, headquartered at 747 Third

1 DR. UWE KORTSHAGEN

2 MR. RISMILLER: Brett Rismiller
3 with White & Case representing Global
4 Foundries.

5 THE VIDEOGRAPHER: And those on
6 the phone, please.

7 MR. ZHOU: Yes, this is Xin-Yi
8 Zhou. It's spelled X-I-N dash Y-I, and the
9 last name is Z-H-O-U, and I represent
10 Advanced Micro Devices, Inc.

11 MR. HOUSTON: This is
12 Michael Houston of Foley & Lardner
13 representing Renesas Electronics Corporation
14 and Renesas Electronics America, Inc.,
15 Renesas being spelled R-E-N-E-S-A-S, for the
16 court reporter.

17 MR. SILLIMAN: Michael Silliman
18 here, last name is S-I-L-L-I-M-A-N, from
19 Baker, Botts, LLP, representing Toshiba.

20 THE VIDEOGRAPHER: And would the
21 court reporter please swear in the witness.

22 DR. UWE KORTSHAGEN,
23 a witness in the above-entitled action,
24 after having been first duly sworn, was
25 deposed and says as follows:

1 DR. UWE KORTSHAGEN
2 Avenue, New York, New York. The court
3 reporter is Amy Larson in association
4 with TSG Reporting.

5 Will counsel please introduce yourselves.

6 MR. LAHAV: Etai Lahav of
7 Radulescu, LLP, representing the patent owner
8 Zond.

9 MS. GRANOVSKY: Maria Granovsky,
10 Radulescu, LLP, representing Zond.

11 MR. GONSALVES: Greg Gonsalves
12 representing Zond.

13 MR. FITZPATRICK: Anthony
14 Fitzpatrick from Duane Morris, LLP,
15 representing Taiwan Semiconductor
16 Manufacturing Company Limited and TSMC
17 North America.

18 MR. TENNANT: David Tennant with
19 White & Case representing Global Foundries.

20 MR. MCCOMBS: David McCombs with
21 Haynes & Boone representing TSMC
22 North America and Taiwan Semiconductor
23 Limited and Fujitsu.

24 MR. HUH: Gregory Huh with
25 Haynes & Boone representing TSMC and Fujitsu.

1 DR. UWE KORTSHAGEN

2 MR. FITZPATRICK: Before we begin
3 the questioning this morning, I did want to
4 state on the record that objections that I
5 make or that Mr. Tennant makes will apply to
6 all petitioners, to avoid having -- us
7 having to make duplicate objections.

8 MR. LAHAV: And we agree with
9 that. And if we could actually limit it to
10 statements from Mr. Fitzpatrick that would be
11 best, but --

12 MR. FITZPATRICK: Our intention is
13 to try to do that to the extent possible.

14 MR. LAHAV: Okay. Thank you.

15 EXAMINATION

16 BY MR. LAHAV:

17 Q. Good morning.

18 A. Good morning.

19 Q. Can you please state your full name for the
20 record.

21 A. My full name is Uwe Richard Kortshagen.

22 Q. And can you spell all of that.

23 A. The first name is spelled U-W-E. The middle
24 name R-I-C-H-R -- A-R-D, and the last name
25

1 DR. UWE KORTSHAGEN
 2 is K-O-R-T-S-H-A-G-E-N.
 3 Q. Have you ever given a deposition before?
 4 A. No.
 5 Q. Okay. So I'm going to go over some of the
 6 rules of depositions, okay?
 7 A. Thank you.
 8 Q. Do you understand that you've just taken an
 9 oath to testify truthfully?
 10 A. Yes.
 11 Q. And you will testify truthfully today?
 12 A. Yes.
 13 Q. You understand that I'm going to be asking
 14 you questions?
 15 A. Yes.
 16 Q. And that you have an obligation to answer my
 17 questions?
 18 A. Yes.
 19 Q. And that even if your counsel objects to my
 20 questions, you still have to answer them; do
 21 you understand that?
 22 A. Yes.
 23 Q. The one exception to that is if you get
 24 instructed on attorney work product or
 25 attorney/client privilege; do you understand?

1 DR. UWE KORTSHAGEN
 2 Q. Is there any other reason why you can't
 3 testify truthfully today?
 4 A. No.
 5 Q. Okay. Where are you currently employed?
 6 A. At the University of Minnesota.
 7 Q. And what is your title?
 8 A. I'm a professor of mechanical engineering.
 9 Q. In your CV you reference a diploma degree in
 10 physics in June of 1988, and it's -- how do
 11 you pronounce the name of the university?
 12 A. The University of Bochum.
 13 Q. Bochum?
 14 A. Bochum.
 15 Q. Bochum. And is a diploma degree like a
 16 bachelor's degree in the United States?
 17 A. It is probably between a bachelor's and a
 18 master's degree. It is a five-year degree.
 19 Q. Okay. Did you -- okay. And then you
 20 obtained a Ph.D. in January of 1991 from the
 21 same university?
 22 A. That is correct, yes.
 23 Q. Did you prepare a dissertation in connection
 24 with your Ph.D.?
 25 A. Yes, I did.

1 DR. UWE KORTSHAGEN
 2 A. Yes.
 3 Q. Please allow me to finish my question before
 4 you answer, okay?
 5 A. Yes.
 6 Q. Thank you. If you don't understand a
 7 question or you would like me to rephrase,
 8 please ask me to do so, okay?
 9 A. Yes.
 10 Q. If I ask a question and you answer it, I'm
 11 going to assume you understood it. Is that
 12 fair?
 13 A. Yes.
 14 Q. Okay. Please also be careful to give
 15 audible, verbal answers to my questions, all
 16 right?
 17 A. Yes.
 18 Q. So uh-huhs or nuh-uhs, the court reporter has
 19 trouble taking those, so it's important to
 20 give the verbal answers, all right?
 21 A. Yes.
 22 Q. Are you taking any medications that might
 23 impair your ability to testify truthfully
 24 today?
 25 A. No.

1 DR. UWE KORTSHAGEN
 2 Q. What was the topic of that dissertation?
 3 A. The topic was on electron energy distribution
 4 functions in radio frequency produced
 5 plasmas.
 6 Q. Did you study any particular applications?
 7 A. I studied a particular method of generating
 8 plasmas based on so-called propagating
 9 surface waves.
 10 Q. And did you -- did you study any particular
 11 commercial application or application of any
 12 particular endeavor other than the
 13 generalized -- generation of plasmas?
 14 A. No.
 15 Q. Okay. Did that dissertation entail research
 16 relating to generation of plasmas inside a
 17 magnetron?
 18 A. No.
 19 Q. Did you study in your dissertation generating
 20 plasmas for purposes of sputtering?
 21 A. No.
 22 Q. After your Ph.D., under education your CV
 23 lists a, quote, habilitation in experimental
 24 physics?
 25 A. That is correct.

DR. UWE KORTSHAGEN

- 1 Q. What is a habilitation in experimental
2 physics?
3
4 A. Habilitation is a specific degree in the
5 German academic system which at that time in
6 the 1990s was required to become a
7 university professor.
8 Q. Does it correlate with post-doc research?
9 A. Yeah, you may correlate it with -- with an
10 advanced post doc. It also includes writing
11 yet another thesis, habilitation, but one is
12 already in the position to advise Ph.D.
13 students at that point.
14 Q. Was there any coursework required --
15 A. No, there is no --
16 Q. Go ahead.
17 A. No, there is no coursework required.
18 Q. What was the topic of your thesis for your
19 habilitation?
20 A. The topic of the thesis was on kinetic theory
21 and experiments studying electron
22 distribution functions in a wide range of
23 plasmas.
24 Q. In that, quote, "wide range of plasmas," end
25 quote, did that include plasmas used for

DR. UWE KORTSHAGEN

- 1 When -- when people in the art talk about
2 chemical vapor deposition, that's something
3 different than sputtering, correct?
4
5 A. Generally, I would say this is correct, yes.
6 Q. So you said you studied this capacitively?
7 coupled plasmas that could be used for
8 sputtering. Did you study them in connection
9 with their use for sputtering?
10 A. I studied them with respect to their -- how
11 should I express it -- with respect to the
12 properties of electrons within these plasmas,
13 in particular, the energy distribution
14 function of electrons.
15 Q. But you didn't study how to make use of that
16 energy distribution function with respect to
17 sputtering, correct?
18 MR. FITZPATRICK: Objection to the
19 form of the question.
20 THE WITNESS: I think the correct
21 way to answer this is to say that the
22 fundamental studies of electron distribution
23 functions that I performed also applied to
24 situations of sputtering.
25 BY MR. LAHAV:

DR. UWE KORTSHAGEN

- 1 sputtering?
2
3 A. Yes.
4 Q. Did it include plasmas used for magnetron
5 sputtering?
6 A. No.
7 Q. Can you explain the work you did in
8 connection with your habilitation related to
9 plasmas used for sputtering?
10 A. Among other -- among the different systems
11 that I studied at that time was a particular
12 plasma system called capacitively coupled
13 plasma, and such kinds of plasmas can be used
14 for the chemical vapor deposition of films,
15 but they can also be used for sputtering.
16 Q. And sputtering is not chemical vapor
17 deposition, correct?
18 A. I would call it more physical vapor
19 deposition.
20 Q. So sputtering is physical vapor deposition
21 and chemical vapor deposition is some other
22 process, right?
23 A. Could you repeat that question, please?
24 Q. Sure. I'm going to repeat it, I'm going
25 to change it.

DR. UWE KORTSHAGEN

- 1 Q. Did you apply them?
2 MR. FITZPATRICK: Objection to the
3 form of the question.
4 THE WITNESS: If you're asking me
5 whether I applied what I learned at the time.
6 to sputtering, the answer is no.
7 BY MR. LAHAV:
8 Q. Did you study how those plasmas might be used
9 for sputtering?
10 A. No.
11 Q. Do you have any industry experience? Have
12 you ever worked in industry?
13 A. No.
14 Q. Have you ever operated a PVD apparatus?
15 A. No.
16 Q. So you've never operated a magnetron
17 sputtering chamber, for example, right?
18 A. No.
19 Q. Have you ever designed a magnetron sputtering
20 chamber?
21 A. No.
22 Q. The focus of your research with respect to
23 plasmas relates to nanoparticles and
24 nanocrystals, correct?
25

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